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PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of

Attn: OIPE

Syo-ichi TAKAMIZAWA et al.

Group Art Unit: 2812

Application No.: 10/578,369

Docket No.: 127101

Filed: May 5, 2006

For: METHOD FOR PRODUCING SILICON EPITAXIAL WAFER

REQUEST FOR CORRECTION OF PALM RECORDS

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

Attached is a photocopy of the original filing receipt on which errors have been corrected in red. These errors are being brought to the attention of the Patent and Trademark Office so that it may correct its records.

Respectfully submitted,

William P. Berridge
Registration No. 30,024

WPB:amb

Date: December 12, 2006

OLIFF & BERRIDGE, PLC
P.O. Box 19928
Alexandria, Virginia 22320
Telephone: (703) 836-6400

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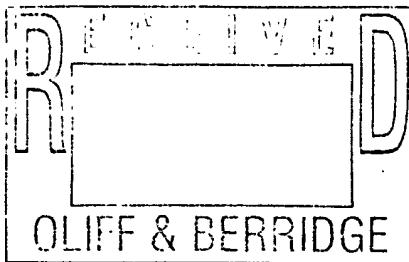
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APPL NO.	FILING OR 371 (c) DATE	ART UNIT	FIL FEE REC'D	ATTY.DOCKET NO	DRAWINGS	TOT CLMS	IND CLMS
10/578,369	05/05/2006	2812	1150	127101	2	25	2

25944
 OLIFF & BERRIDGE, PLC
 P.O. BOX 19928
 ALEXANDRIA, VA 22320



CONFIRMATION NO. 8987

FILING RECEIPT



OC000000021392954

Date Mailed: 12/01/2006

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Applicant(s) *Anaka-shi*
 Syo-ichi Takamizawa, Gunma, JAPAN;
 Ryuji Sayama, Gunma, JAPAN;
Anaka-shi

Power of Attorney: The patent practitioners associated with Customer Number **25944**.

Domestic Priority data as claimed by applicant

This application is a 371 of PCT/JP04/12179 08/25/2004

Foreign Applications

JAPAN 2003-385333 11/14/2003

If Required, Foreign Filing License Granted: 11/28/2006

The country code and number of your priority application, to be used for filing abroad under the Paris Convention, is **US10/578,369**

Projected Publication Date: 03/08/2007

Non-Publication Request: No

Early Publication Request: No

Title

Method for producing silicon epitaxial wafer

Preliminary Class

438

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